

LISTING OF THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Canceled)

2. (Canceled)

3. (Currently Amended) A substrate processing apparatus for processing a substrate with a plurality of processing solutions having different components, comprising:
a holding element provided on a rotating base, for holding a peripheral portion of a substrate to keep said substrate in a substantially-horizontal position;
a rotation element for rotating said substrate held by said holding element about an axis along a substantially-vertical direction;
an atmosphere cutoff plate positioned above said holding element, facing a top surface of said substrate held by said holding element; and
a splash prevention element for receiving said plurality of processing solutions splashed from said peripheral portion of said substrate held by said holding element,
wherein said splash prevention element comprises
a plurality of recovery ducts used for collecting said plurality of processing solutions;
a plurality of guiding members for forming said plurality of recovery ducts so that a vertical spacing of each opening thereof is not less than a distance between said rotating base and said atmosphere cutoff plate; and
a selection element for selecting one of said recovery ducts to be used for collecting a processing solution used in a processing for said substrate, to determine a selected recovery duct,
wherein a level of a [[top]] lower surface of a guiding member used for forming said selected recovery duct is set not lower than a level of a lower surface of said rotating base near an opening of said selected recovery duct; and
wherein a level of a top surface of a guiding member used for forming said selected recovery duct is set not higher than a level of a top surface of said atmosphere cutoff plate.

4. (Previously Presented) The substrate processing apparatus according to claim 3, wherein

said selected recovery duct has a shape curving downward, going away from a substrate with a vertical spacing almost equal to a vertical spacing of an opening thereof.

5. (Previously Presented) The substrate processing apparatus according to claim 3, wherein

said selected recovery duct guides one of said plurality of processing solutions downward almost around a substrate.

6. (Previously Presented) The substrate processing apparatus according to claim 3, further comprising

a suck element communicated with said selected recovery duct, for sucking said one of said plurality of processing solutions.

7. (Previously Presented) The substrate processing apparatus according to claim 3, wherein

said rotating base and said atmosphere cutoff plate each have a disk-like shape and respective edge portions thereof facing said plurality of recovery ducts are vertical slide surfaces.

8. (Previously Presented) The substrate processing apparatus according to claim 3, wherein

respective openings of said plurality of recovery ducts which are vertically stacked are disposed at almost the same position in a vertical direction.